CLAIMS

1. A method for producing a polishing slurry including polishing abrasive particles for use in processing for polishing a glass substrate, comprising:

adding processing in which binders and a polysaccharide are added to a raw-material slurry including raw-material abrasive particles serving as a raw material for the polishing abrasive particles, the binders including silica particles in which an average particle diameter is 3 to 20 nm, and the polysaccharide being a binder aggregation suppressing agent for suppressing aggregation of the binders;

drying processing in which the raw-material slurry including the binders and the polysaccharide is dried to produce a mass of the raw-material abrasive particles including the binders and the polysaccharide, the binders being dispersed in the mass of the raw-material abrasive particles via the polysaccharide; and

firing processing in which the mass of the raw-material abrasive particles is fired and a gap is formed in a portion of the mass of the raw-material abrasive particles where the polysaccharide was located due to at least a portion of the polysaccharide being eliminated to produce a cluster of the raw-material abrasive particles including the binders;

wherein the raw-material abrasive particles are bonded via the binders in the cluster of the raw-material abrasive particles.

2. The method for producing a polishing slurry according to claim 1, further comprising crushing processing in which the cluster of the raw-material abrasive particles is crushed to produce the polishing abrasive particles,

wherein an average particle diameter of the polishing abrasive particles produced by the crushing processing is 0.5 to 10 μm.

3. The method for producing a polishing slurry according to claim 1 or 2, wherein the firing is performed at a temperature of 800°C or less.

4. The method for producing a polishing slurry according to any one of claims 1 to 3, wherein in the drying processing, the raw-material slurry including the binders and the polysaccharide is dried through spray-drying.

5. The method for producing a polishing slurry according to any one of claims 1 to 4, wherein the raw-material slurry includes ceria particles that were used in processing for polishing a glass substrate.

6. The method for producing a polishing slurry according to any one of claims 1 to 5, wherein an average particle diameter of the raw-material abrasive particles is 0.3 to 2 μm.

7. A method for manufacturing a glass substrate, comprising a step of producing a polishing slurry according to any one of claims 1 to 6, and a step of polishing a surface of the glass substrate using the polishing slurry.